

Electronic Supplementary Information

Hybrids of iridium-cobalt phosphate as a highly efficient electrocatalyst for oxygen evolution reaction in neutral solution

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Experimental Section

Materials

Cobalt nitrate hexahydrate ($\text{Co}(\text{NO}_3)_2 \cdot 6\text{H}_2\text{O}$, 98.5%), iridium(III) chloride hydrate ($\text{IrCl}_3 \cdot x\text{H}_2\text{O}$, 99.9%), potassium dihydrogen phosphate (KH_2PO_4 , 99.5%) and dipotassium hydrogen phosphate (K_2HPO_4 , 99.5%) were purchased from Alfa Aesar Chemicals. Fluorine-doped tin oxide (FTO) substrates ($8 \text{ } \Omega/\text{square}$, transmittance of 80%) were purchased from Asahi Glass, Tokyo, Japan. All the chemicals used in this work were of analytical grade without further purification. All aqueous solutions in this work were prepared with deionized water ($18 \text{ M}\Omega \text{ cm}$).

Preparation of Co-Pi, Ir-Pi, and IrCo-Pi on glass carbon electrode

The Co-Pi, Ir-Pi, and IrCo-Pi catalysts were prepared on a glass carbon (GC) or FTO electrode via a cyclic voltammetric deposition method, which was different from the potentiostatic deposition¹ usually employed to grow metal phosphate films on conductive substrates. In detail, CV deposition were performed on GC (or FTO) electrode (0.5 cm in diameter) for required cycles in the potential range from -0.04 V to 1.15 V (vs. SCE) at a scan rate of 0.05 V s^{-1} in 0.1 M potassium phosphate buffer solution (PBS, pH 7.0) containing different precursors. For the preparation of Co-Pi and Ir-Pi, the deposition solution contained 0.5 mM $\text{Co}(\text{NO}_3)_2$ and 0.5 mM IrCl_3 , respectively. While for the growth of the IrCo-Pi hybrids, mixed solution of $\text{Co}(\text{NO}_3)_2$ and IrCl_3 was used with a constant $\text{Co}^{2+} + \text{Ir}^{3+}$ concentration of 0.5 mM. The Ir-to-Co molar ratio ($R_{\text{Ir-to-Co}}$) of the deposition solution was varied to modulate the concentrations of Ir and Co in the obtained IrCo-Pi hybrid film. All electrochemical deposition were performed on a CHI660 electrochemical work station (CH Instruments Co., USA) in a three-electrode cell with a saturated calomel electrode (SCE) and a graphite rod as the reference and counter electrodes, respectively.

Material characterization

X-ray diffraction (XRD) patterns of Co-Pi, Ir-Pi and IrCo-Pi were recorded on a D/MAX-2500 Advance powder X-ray diffractometer (Rigaku Co., Japan) with Cu K α radiation operating at 40 kV and 200 mA. Field-emission scanning electron microscopy (SEM) (JSM7500, JEOL Ltd., Japan) was employed to characterize the morphology and atomic composition of all samples, and the SEM images and energy dispersive spectra were obtained at an accelerating voltage of 3 kV and 20 kV, respectively. X-ray photoelectron spectroscopic (XPS) measurements were performed with an ESCALAB 250Xi instrument (ThermoFischer Co., USA) to characterize the surface composition and chemical states of Co-Pi, Ir-Pi and IrCo-Pi.

Electrochemical measurements

Electrochemical measurements were performed on a CHI660C workstation (CH Instruments Co., USA) in a three-electrode system, in which a freshly deposited IrCo-Pi (or Ir-Pi, or Co-Pi), an SCE, and a graphite rod were employed as the working, the reference, and the counter electrodes, respectively. Unless specified, all the potentials in this work were reported with respect to the reversible hydrogen electrode (RHE) on the basis of the following equation:

$$E(\text{V vs. RHE}) = E(\text{V vs. SCE}) + 0.244 + 0.0592\text{pH} \quad (1)$$

where $E(\text{V vs. RHE})$ and $E(\text{V vs. SCE})$ are potentials with respect to RHE and SCE, respectively. Linear sweep voltammetry (LSV) was conducted in the potential range of 1.3 - 1.8 V (vs. RHE) in 0.1 M PBS (pH 7.0) with a scan rate of 5 mV s⁻¹. Electrochemical impedance spectroscopic (EIS) measurements were operated at 1.5 V (vs. RHE) with a frequency range from 106 to 0.01 Hz and an AC amplitude of 5 mV. The double layer capacitance of different samples were measured by CV at the potential sweep rate of 0.005, 0.010, 0.025, 0.05, 0.1, 0.2, 0.4, and 0.8 V s⁻¹. The real electrochemical surface areas (ECSA) of different samples were obtained according to the follow equation:²

$$\text{ECSA} = I_c / (\nu C_{dl}) \quad (2)$$

where I_c is the charging current, ν is potential sweep rate, and C_{dl} is the normalized double layer capacitance of in $\mu\text{F cm}^{-2}$, which is estimated to be 230 $\mu\text{F cm}^{-2}$. All electrochemical data reported in this work was **not** iR compensated.

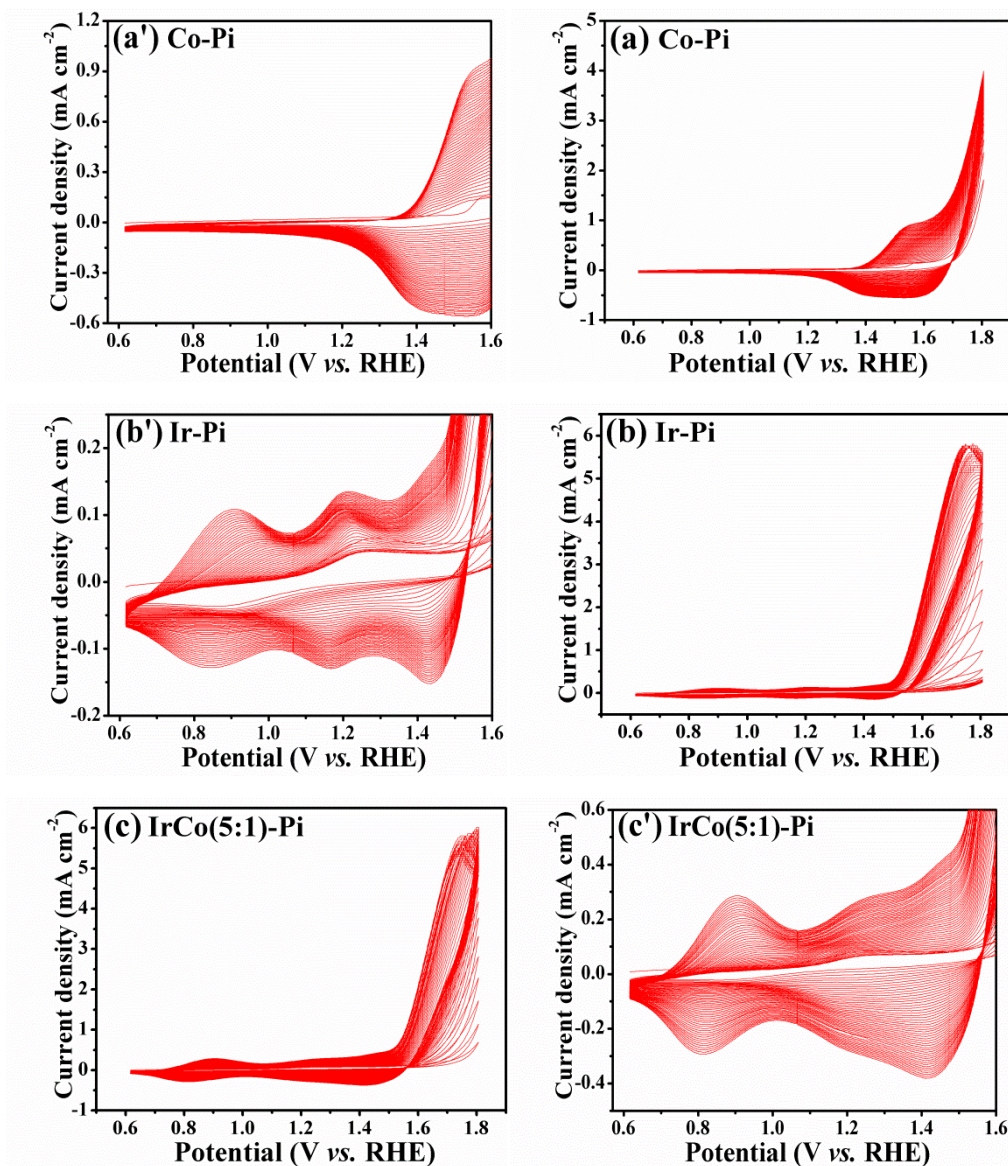


Figure S1. Cyclic voltammograms of the deposition process on GC electrodes in 0.1 M PBS (pH 7.0) containing (a) 0.5 mM Ir³⁺; (b) 0.5 mM Co²⁺; (c) 0.417 mM Ir³⁺ and 0.083 mM Co²⁺. (a'),(b'), and (c') are the corresponding zoom-in images of (a), (b), and (c), respectively.

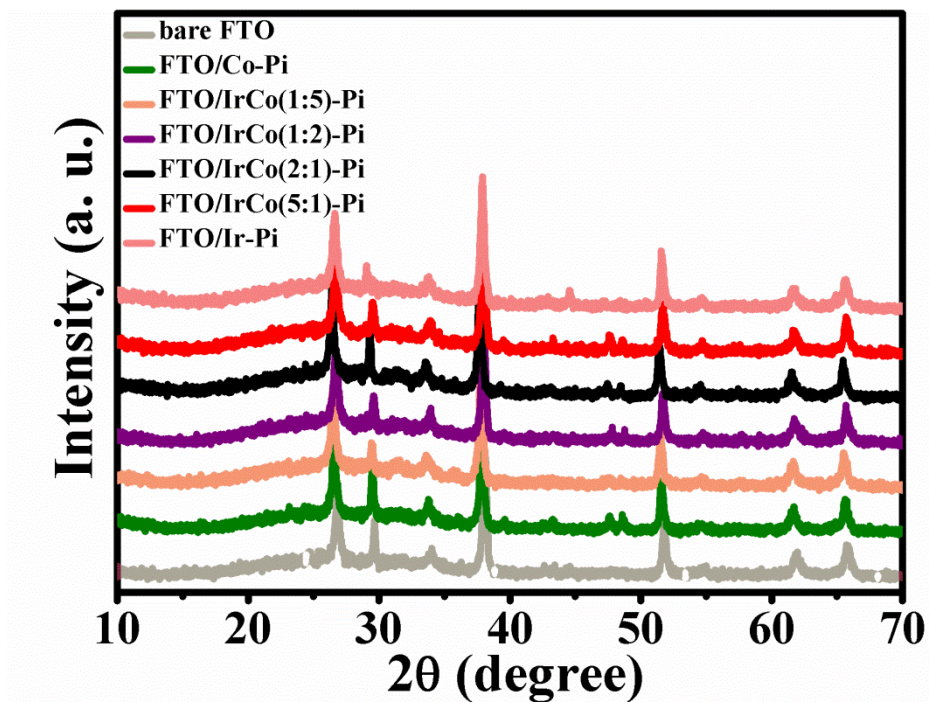


Figure S2. XRD patterns of bare FTO, FTO/Co-Pi, FTO/Ir-Pi, and FTO/IrCo-Pi with different $R_{\text{Ir-to-Co}}$.

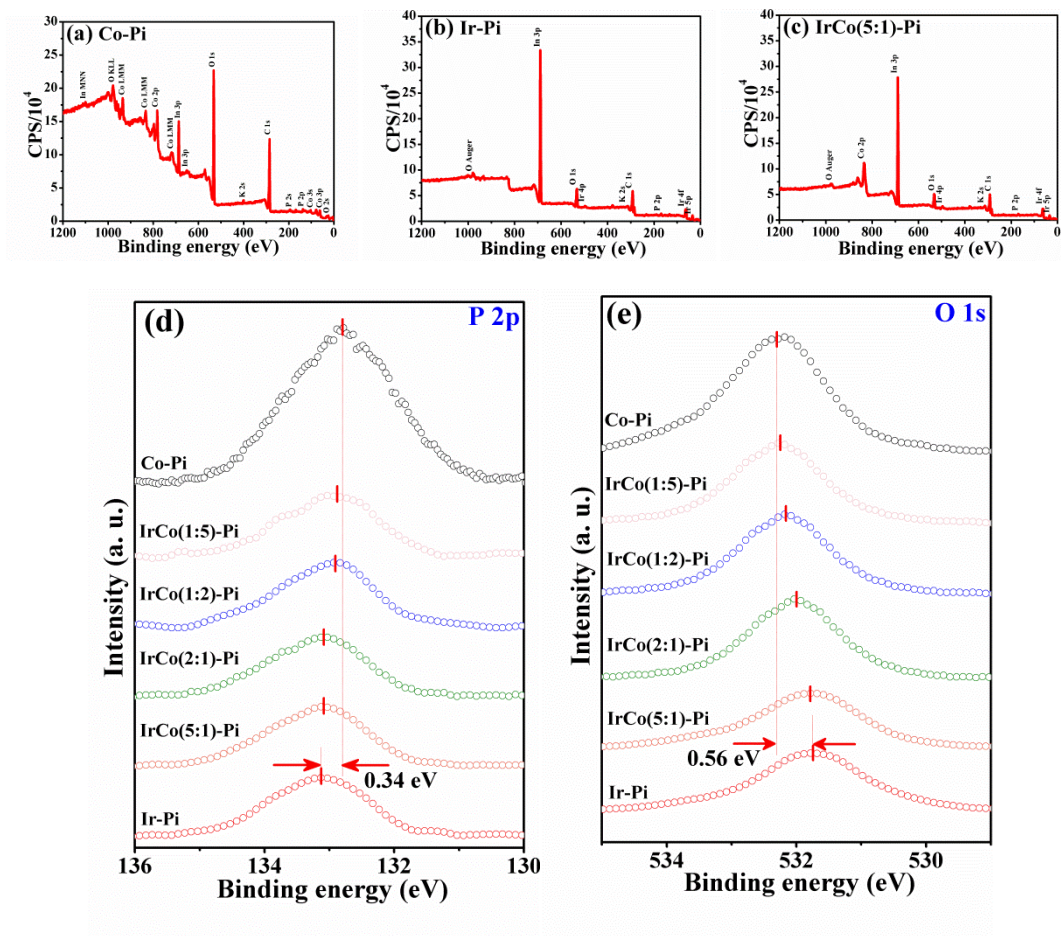


Figure S3. XPS survey spectra of (a) Co-Pi; (b) Ir-Pi; (c) IrCo(5:1)-Pi; high resolution XPS spectra of (d) P 2p; (e) O 1s in Co-Pi, Ir-Pi and IrCo-Pi.

The binding energy of P 2p peaks from Co-Pi and Ir-Pi are 132.79 and 133.13 eV, respectively. The P 2p signal originates from the phosphate ions.^{1,2} The binding energy of O 1s peaks from Co-Pi and Ir-Pi are 532.31 and 531.75 eV, respectively. The O 1s signal originates from the interaction between the metal and the absorbed oxygen species.^{1,3} In addition, the positive shift of O 1s peak position from Ir-Pi to IrCo-Pi and then to Co-Pi suggest partial electron transfer along Ir-O-Co bond.

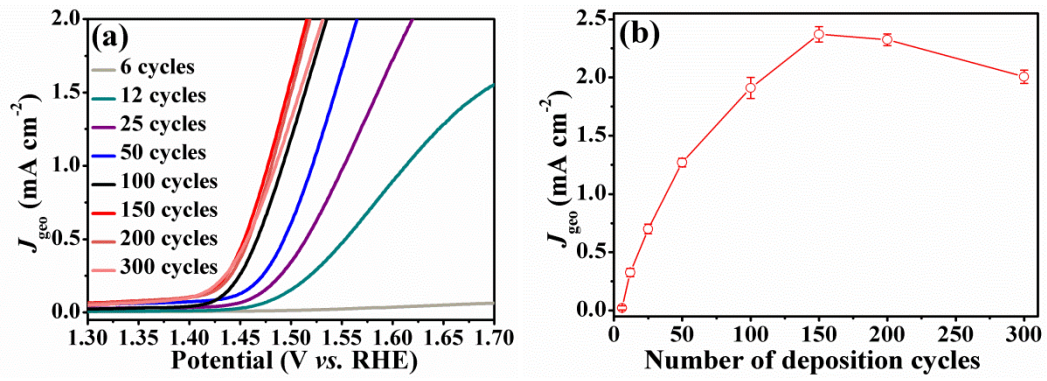


Figure S4. (a) Linear sweep voltammetry (LSV) curves of IrCo(5:1)-Pi prepared by CV co-deposition for different cycles; (b) The influence of IrCo(5:1)-Pi deposition cycle on the current density. The current density was obtained from (a) at an overpotential of 300 mV (1.53 V vs. RHE). The error bar in (b) comes from the variation of data obtained on different IrCo(5:1)-Pi samples prepared with the same deposition cycles.

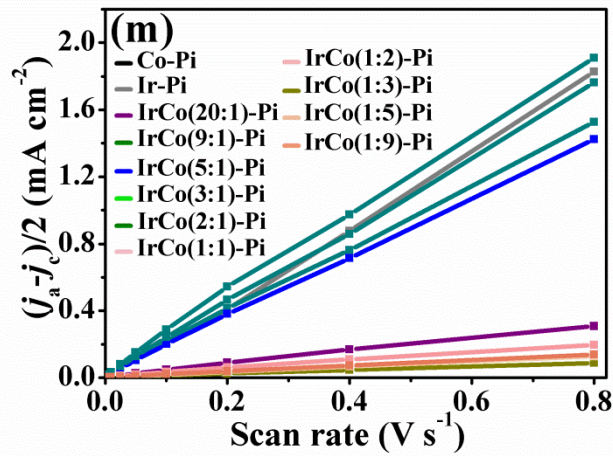
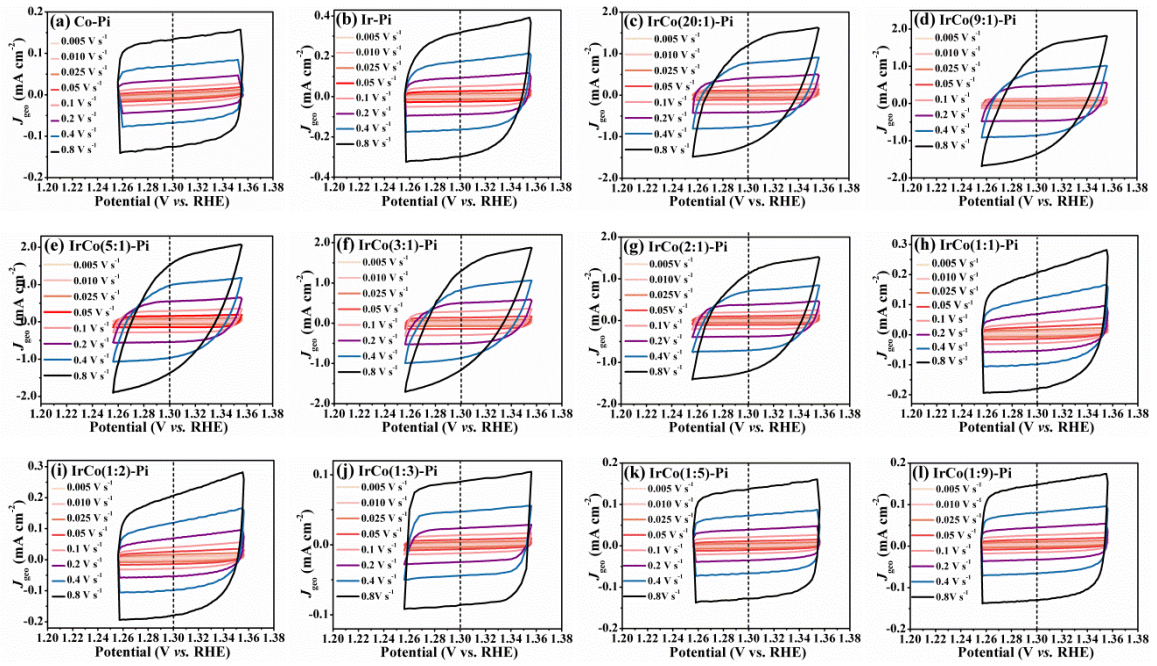
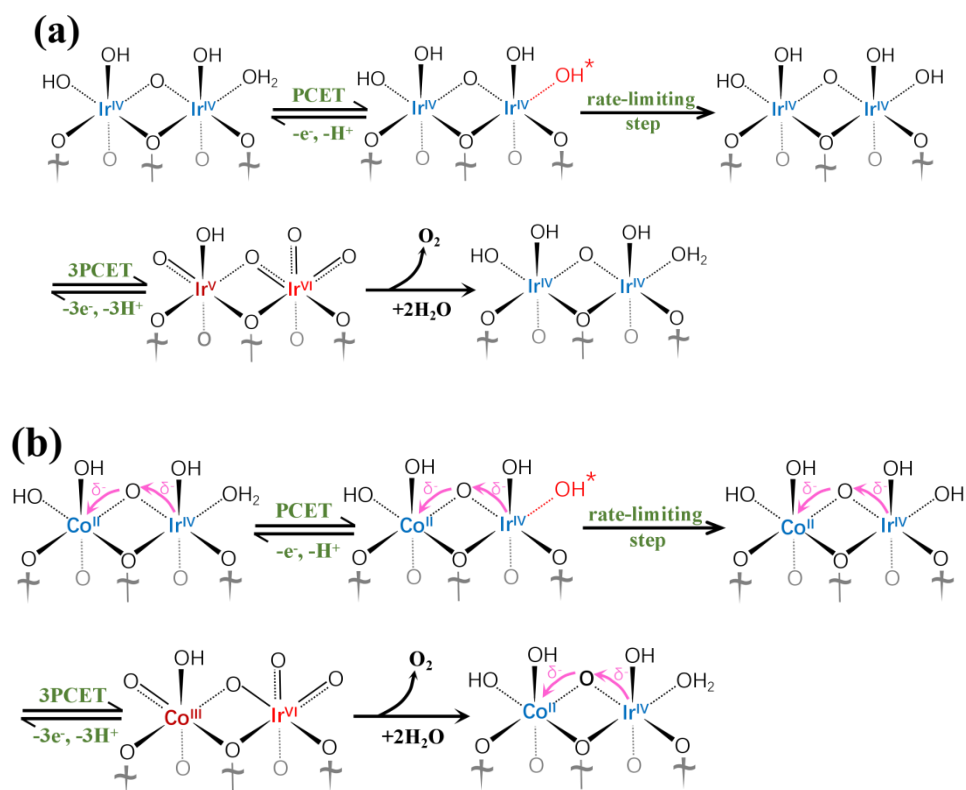


Figure S5. Cyclic voltammograms of (a) Co-Pi, (b) Ir-Pi, and (c)-(l) IrCo-Pi in an OER inert potential window at different scan rates, (m) The linear fitting extraction of the double-layer capacitance of all samples.



Scheme S1 Schematics of OER mechanisms on (a) Ir-Pi and (b) IrCo-Pi. Pink arrows show the partial electron transfer direction.

Table S1. Ir-to-Co molar ratio obtained by XPS on the surface of Co-Pi, Ir-Pi and IrCo-Pi catalysts.

Sample	Ir-to-Co molar ratio in deposition solution for the preparation of catalyst	Ir-to-Co molar ratio on the surface of catalyst
Ir-Pi	1:0	1:0
IrCo(5:1)-Pi	5:1	1:1.01
IrCo(2:1)-Pi	2:1	1:4.90
IrCo(1:2)-Pi	1:2	1:10.70
IrCo(1:5)-Pi	1:5	1:22.85
Co-Pi	0:1	0:1

Table S2. Comparison of electrocatalytic OER performance of the IrCo-Pi hybrids with different Ir-to-Co molar ratio ($R_{\text{Ir-to-Co}}$). All samples in this table were prepared by deposition for 50 cycles.

Ir-to-Co ratio	η_{onest} (mV)	J_{geo} (mA cm ⁻²) @ $\eta=300$ mV	J_{ECSA} (mA cm ⁻²) @ $\eta=300$ mV	Tafel slope (mV dec ⁻¹)	ECSA (cm ²)
Ir-Pi	285	0.40	0.17	57.1	0.32
IrCo(20:1)-Pi	282	0.49	0.19	60.8	1.61
IrCo(9:1)-Pi	248	1.17	0.29	50.9	1.87
IrCo(5:1)-Pi	246	1.21	0.32	58.6	2.07
IrCo(3:1)-Pi	256	0.99	0.24	57.3	1.83
IrCo(2:1)-Pi	259	0.87	0.18	57.0	1.32
IrCo(1:1)-Pi	287	0.33	0.15	61.0	0.20
IrCo(1:2)-Pi	305	0.21	0.13	82.9	0.15
IrCo(1:3)-Pi	393	0.09	0.12	131.1	0.09
IrCo(1:5)-Pi	408	0.10	0.11	133.9	0.14
IrCo(1:9)-Pi	402	0.11	0.12	148.9	0.15
Co-Pi	418	0.12	0.06	129.8	0.14

Table S3. Comparison of electrocatalytic OER performance of IrCo(5:1)-Pi with those reported on other transition metal phosphate catalysts.

Substrate	Catalyst	Electrolyte, pH	η_{onest} (mV)	Tafel slope (mV dec ⁻¹)	Reference
GC	Optimized IrCo(5:1)-Pi	0.1 M PBS, pH 7	208	51.4	This work
ITO	Co-Pi	0.1 M PBS, pH 7	280	60	1
CC	Co-Pi	0.1 M PBS, pH 7	340	60	3
CC	Ir-Pi	0.1 M PBS, pH 7	220	55	3
CP	Co-Ac-Pi	0.1 M PBS, pH 7	324	103	4
Ti mesh	Co-Pi	0.1 M PBS, pH 7	176	187	5
CC	Fe-Bi-Pi	0.1 M PBS, pH 7	322	94	6
FTO	Mn ₃ (PO ₄) ₂	0.5 M Na-Pi, pH 7	434	120	7
CC	Ni-Bi-Pi	0.1 M K-Bi, pH 9.2	220	139	8
GC	Co-Pi	0.1 M KOH, pH 13.2	346	83	9
GC	CoFe-Pi	0.1 M KOH, pH 13.2	252	33	10
GC	Mn-Pi	0.1 M KOH, pH 13.2	243	47	11
GC	CoFe-Pi	1 M KOH, pH 13.8	235	30	12
CP	FeCo-Pi	1 M KOH, pH 13.8	260	36	13
Ni foam	CoNi-Pi	1 M KOH, pH 13.8	163	59	14
NiFe foam	NiFe-Pi/NiFeP	1 M KOH, pH 13.8	188	57	15
GC	FeP/Fe-Pi	1 M KOH, pH 13.8	290	48	16
Ni foam	Fe-Pi	1 M KOH, pH 13.8	220	70	17
Ni foam	Fe ₂ PO ₅	1 M KOH, pH 13.8	227	27	18
Ni foam	Fe-Pi	1 M KOH, pH 13.8	247	28	19
Ni foam	NiFe-Pi	1 M KOH, pH 13.8	237	37	20
Ni foam	Ni ₂ P ₂ O ₇	1 M KOH, pH 13.8	211	52	21
GC	Fe(OH) ₃ /Ni-Pi	1 M KOH, pH 13.8	242	45	22
Ti foam	Ni ₁₂ P ₅ /Ni ₃ (PO ₄) ₂	1 M KOH, pH 13.8	268	52	23

Note: GC=glassy carbon electrode. ITO=indium-doped tin oxide. CC= carbon cloth. CP=carbon paper. FTO=fluorine-doped tin oxide.

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